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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/633,055	07/31/2003	Shahriar Ahmed	42P10970C	3607

7590 03/26/2007
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BLAKELY, SOKOLOFF, TAYLOR & ZAFMAN LLP
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Seventh Floor, CA 90025

EXAMINER

IM, JUNGHWA M

ART UNIT	PAPER NUMBER
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2811

SHORTENED STATUTORY PERIOD OF RESPONSE	MAIL DATE	DELIVERY MODE
3 MONTHS	03/26/2007	PAPER

Please find below and/or attached an Office communication concerning this application or proceeding.

If NO period for reply is specified above, the maximum statutory period will apply and will expire 6 MONTHS from the mailing date of this communication.

<p align="center">Office Action Summary</p>	<p>Application No.</p> <p>10/633,055</p>	<p>Applicant(s)</p> <p>AHMED ET AL.</p>	
	<p>Examiner</p> <p>Junghwa M. Im</p>	<p>Art Unit</p> <p>2811</p>	

-- The MAILING DATE of this communication appears on the cover sheet with the correspondence address --
Period for Reply

A SHORTENED STATUTORY PERIOD FOR REPLY IS SET TO EXPIRE 3 MONTH(S) FROM THE MAILING DATE OF THIS COMMUNICATION.

- Extensions of time may be available under the provisions of 37 CFR 1.136(a). In no event, however, may a reply be timely filed after SIX (6) MONTHS from the mailing date of this communication.
- If the period for reply specified above is less than thirty (30) days, a reply within the statutory minimum of thirty (30) days will be considered timely.
- If NO period for reply is specified above, the maximum statutory period will apply and will expire SIX (6) MONTHS from the mailing date of this communication.
- Failure to reply within the set or extended period for reply will, by statute, cause the application to become ABANDONED (35 U.S.C. § 133). Any reply received by the Office later than three months after the mailing date of this communication, even if timely filed, may reduce any earned patent term adjustment. See 37 CFR 1.704(b).

Status

- 1) ☒ Responsive to communication(s) filed on 26 December 2006.
- 2a) ☐ This action is **FINAL**. 2b) ☒ This action is non-final.
- 3) ☐ Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under *Ex parte Quayle*, 1935 C.D. 11, 453 O.G. 213.

Disposition of Claims

- 4) ☒ Claim(s) 13,17-22 and 27-31 is/are pending in the application.
- 4a) Of the above claim(s) _____ is/are withdrawn from consideration.
- 5) ☐ Claim(s) _____ is/are allowed.
- 6) ☐ Claim(s) _____ is/are rejected.
- 7) ☒ Claim(s) 13,17-22 and 27-31 is/are objected to.
- 8) ☐ Claim(s) _____ are subject to restriction and/or election requirement.

Application Papers

- 9) ☐ The specification is objected to by the Examiner.
- 10) ☐ The drawing(s) filed on _____ is/are: a) ☐ accepted or b) ☐ objected to by the Examiner.
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).
- 11) ☐ The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.

Priority under 35 U.S.C. § 119

- 12) ☐ Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).
a) ☐ All b) ☐ Some * c) ☐ None of:
1. ☐ Certified copies of the priority documents have been received.
 2. ☐ Certified copies of the priority documents have been received in Application No. _____.
 3. ☐ Copies of the certified copies of the priority documents have been received in this National Stage application from the International Bureau (PCT Rule 17.2(a)).

* See the attached detailed Office action for a list of the certified copies not received.

Attachment(s)

- | | |
|--|---|
| 1) <input checked="" type="checkbox"/> Notice of References Cited (PTO-892) | 4) <input type="checkbox"/> Interview Summary (PTO-413)
Paper No(s)/Mail Date. _____ |
| 2) <input type="checkbox"/> Notice of Draftsperson's Patent Drawing Review (PTO-948) | 5) <input type="checkbox"/> Notice of Informal Patent Application (PTO-152) |
| 3) <input type="checkbox"/> Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08)
Paper No(s)/Mail Date _____ | 6) <input type="checkbox"/> Other: _____ |

DETAILED ACTION

Double Patenting

The nonstatutory double patenting rejection is based on a judicially created doctrine grounded in public policy (a policy reflected in the statute) so as to prevent the unjustified or improper timewise extension of the "right to exclude" granted by a patent and to prevent possible harassment by multiple assignees. See *In re Goodman*, 11 F.3d 1046, 29 USPQ2d 2010 (Fed. Cir. 1993); *In re Longi*, 759 F.2d 887, 225 USPQ 645 (Fed. Cir. 1985); *In re Van Ornum*, 686 F.2d 937, 214 USPQ 761 (CCPA 1982); *In re Vogel*, 422 F.2d 438, 164 USPQ 619 (CCPA 1970); and, *In re Thorington*, 418 F.2d 528, 163 USPQ 644 (CCPA 1969).

A timely filed terminal disclaimer in compliance with 37 CFR 1.321(c) may be used to overcome an actual or provisional rejection based on a nonstatutory double patenting ground provided the conflicting application or patent is shown to be commonly owned with this application. See 37 CFR 1.130(b).

Effective January 1, 1994, a registered attorney or agent of record may sign a terminal disclaimer. A terminal disclaimer signed by the assignee must fully comply with 37 CFR 3.73(b).

Claims 1-4, 6-9, 11-14, 16-19, 21-24, 26-29 and 31-34 are rejected on the ground of nonstatutory obviousness-type double patenting as being unpatentable over claims 1-40 of U.S. Patent No. 6,703,685 in view of U.S. Patent No. 4,982,257 to Akbar et al. (Akcar).

The conflicting claims are substantially identical in structure and material wise. In a comparison of pending claim 13, for example, and claim 10 of '685 patent, the substantial difference is that pending claim 13 requires a limitation of "an emitter cut provided at the bottom of said emitter stack and on top of an intrinsic base structure formed in the substrate." However, Fig. 8 of Akbar shows an emitter cut (an emitter/base junction) provided at the bottom of said emitter stack and on top of an intrinsic base structure (a portion of the base in contact with the emitter) formed in the substrate.

It would have been obvious to one of ordinary skill in the art at the time of the invention to incorporate the teachings of Akbar to the device of '239 patent in order to have an emitter cut

Art Unit: 2811

provided at the bottom of said emitter stack and on top of an intrinsic base structure formed in the substrate to reduce the device size.

Claims 17, 27 and 31 are substantially identical to claims 11, 13 and 14 of '685 patent.

Regarding claim 18, Fig. 8 of Akbar shows a bipolar junction transistor further including:
a collector structure 12 disposed in the substrate below the emitter stack; and
an intrinsic base structure 14 disposed between the emitter stack 16 and the collector structure 12.

Regarding claim 19, Fig. 8 of Akbar shows a bipolar junction transistor further including:
a collector structure 12 disposed in the substrate below the emitter stack; and
a dielectric layer 18, 20 disposed above the substrate and below the emitter stack and above the collector structure; and
an intrinsic base structure 14 disposed between the emitter stack and the collector structure.

Fig. 8 of Akbar shows most aspect of the instant invention except "the dielectric layer is patterned for said emitter cut to be formed therein." Fig. 9 of Harame shows a semiconductor device wherein the dielectric layer 34, 36 is patterned for the emitter cut (a bottom portion of the emitter 40) to be formed therein. It would have been obvious to one of ordinary skill in the art at the time of the invention to incorporate the teachings of Harame into the device of Akbar in order to have to a semiconductor device wherein the dielectric layer patterned for the emitter cut to reduce parasite capacitance between the emitter and the extrinsic base.

Regarding claim 20, Fig. 8 of Akbar shows a collector tap 26 is N type.

Regarding claim 21, Akbar discloses that the substrate includes a BiCMOS structure (col. 1, lines 11-14).

Regarding claim 22, Fig. 8 of Akbar shows the BJT is selected from a monojunction BJT device and a heterojunction BJT device.

Regarding claim 28, Fig. 8 of Akbar shows the bipolar junction transistor is an NPN transistor, and the collector tap is N type.

Regarding claim 29, Akbar discloses the bipolar junction transistor is an PNP transistor, and the collector tap is P type (col. 3, lines 24-25).

Regarding claim 30, Fig. 8 of Akbar shows the collector tap has no doping that is different from the substrate.

Response to Arguments

Applicant's arguments with respect to pending claims have been considered but are moot in view of the new ground(s) of rejection.

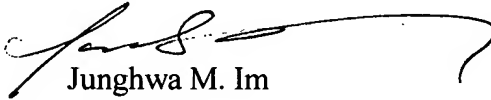
Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Junghwa M. Im whose telephone number is (571) 272-1655. The examiner can normally be reached on MON.-FRI. 8:30AM-5:00PM.

Art Unit: 2811

If attempts to reach the examiner by telephone are unsuccessful, the examiner's acting supervisor, Richard T. Elms can be reached on (571) 272-1869. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see <http://pair-direct.uspto.gov>. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).



Junghwa M. Im
Examiner
Art Unit 2811

jmi